

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Original) A lithographic projection apparatus comprising:
an illumination system to provide a beam of radiation;
an article support to support an article to be placed in a beam path of said beam of radiation; and
a clamp to clamp said article to said article support,
wherein said clamp is provided with a plurality of zones located around a circumference of said article support to create a locally adjusted pressure so as to provide a local bending moment to locally bend said article.
2. (Original) A lithographic projection apparatus according to claim 1, wherein said article support comprises at least three support pillars.
3. (Original) A lithographic apparatus according to claim 2, wherein said article support consists of three pillars.
4. (Original) A lithographic apparatus according to claim 2, wherein said article support consists of four support pillars.
5. (Original) A lithographic apparatus according to claim 2, wherein said support pillars are actuatable.
6. (Original) A lithographic apparatus according to claim 5, wherein said support pillars are piezo-pads.

7. (Original) A lithographic apparatus according to claim 1, wherein at least one of said plurality of zones comprises an individually controllable clamp.

8. (Original) A lithographic apparatus according to claim 7, wherein said clamp comprises a height sensor to sense a local height of the article.

9. (Original) A lithographic apparatus according to claim 1, further comprising a clamp control unit to adjust the clamping pressure of said plurality of zones to attain a leveled article.

10. (Original) A lithographic apparatus according to claim 9, wherein said clamp control unit is configured to control said clamping pressure in response to at least one of a detected local height of said article and a detected image quality.

11. (Original) A lithographic apparatus according to claim 1, wherein said plurality of zones comprise sectioned pressure zones to create a relatively differing backfill gas pressure.

12. (Original) A lithographic apparatus according to claim 1, wherein said article comprises a reticle.

13. (Currently Amended) An article support to support a flat article to be placed in a beam path of radiation, said article support comprising:

a clamp to clamp said article to said article support,

wherein said clamp is provided with a plurality of zones located around a circumference of said article support to create a locally adjusted pressure so as to provide a local bending moment to locally bend said article.

Claims 14 – 18 (Canceled).